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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Salvatore Pavone

Serial No.: N/A

Filed: Herewith

For: A THREE-STEP CHAMBER CLEANING PROCESS FOR
DEPOSITION TOOLS

Group No.: N/A

Examiner: N/A

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

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Pursuant to the duty of disclosure under 37 C.F.R. § 1.56, Applicant submits this statement.

This submittal is made in accordance with 37 C.F.R. §§ 1.97 and 1.98 and § 609 of the Manual of Patent Examining Procedure. The patents, publications and other information herein are listed below and on the attached Form PTO-1449. Copies of the listed references are submitted herewith.

<u>U.S. Patent No.</u>	<u>Inventor</u>	<u>Date</u>
6,534,423	Turner	March 18, 2003
6,397,861	Wing et al.	June 4, 2002

References:

DuPont Zyron - Electronic Gases, Technical Bulletin; www.dupont.com/zyron

M.T. Mocella; "RECENT STUDIES OF c-C4F8, AN OPTIMUM FLUOROCARBON GAS FOR CVD CHAMBER CLEANING"; www.dupont.com/zyron/pdf/isesh_2001.pdf.

T.Nishikawa, M. Kataoka, S. Kesari, OL. Zazzera, L. Tousignant; "PROCESS COMPARISONS DURING C3F8 AND C2F6 CVD CHAMBER CLEANING AT ASM JAPAN"; www.asm.com/pdf/chambclean01.pdf.

Allen Evans, Lance Nevala, Charles C. Allgood; "ADVANCES IN REDUCING PFC EMISSIONS AND GAS COSTS: QUALIFICATION AND IMPLEMENTATION OF C-C4F8 CHAMBER CLEAN GAS IN A NOVELLUS CONCEPT-2 CHEMICAL VAPOR DEPOSITION TOOL"; www.dupont.com/zyron/pdf/southwest_2002.pdf.

"REDUCING PFC EMISSIONS; A TECHNOLOGY UPDATE"; 1/7/2000 Future Fab Volume 9; Montgomery Research, Inc.; www.future-fab.com/documents.asp?grID=273&d_ID=1184.

Applicant hereby expressly reserves the right to swear behind the effective dates of any of the above Patents and to question the relevance and materiality of the Patents and Publications listed herein, in whole, in part, or in combination, subsequent to filing this Information Disclosure

Statement. The Commissioner is hereby authorized to charge any fees which may be required, or credit any overpayment to Deposit Account No. 20-0668.

Respectfully submitted,

HITT GAINES, P.C.

A handwritten signature in black ink, appearing to read "Greg H. Parker", written over a horizontal line.

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				Application Number	N/A
				Filing Date	Herewith
				First Named Inventor	Salvatore Pavone
				Art Unit	N/A
				Examiner Name	N/A
Sheet	2	of	2	Attorney Docket Number	TI 35748

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	/	DuPont Zyron - Electronic Gases, Technical Bulletin; www.dupont.com/zyron	
	/	M.T. Mocella; "RECENT STUDIES OF c-C4F8, AN OPTIMUM FLUOROCARBON GAS FOR CVD CHAMBER CLEANING"; /www.dupont.com/zyron/pdf/isesh_2001.pdf .	
	/	T.Nishikawa, M. Kataoka, S. Kesari, OL. Zazzera, L. Tousignant; "PROCESS COMPARISONS DURING C3F8 AND C2F6 CVD CHAMBER CLEANING AT ASM JAPAN"; www.asm.com/pdf/chambclean01.pdf .	
	/	Allen Evans, Lance Nevala, Charles C. Allgood; "ADVANCES IN REDUCING PFC EMISSIONS AND GAS COSTS: QUALIFICATION AND IMPLEMENTATION OF C-C4F8 CHAMBER CLEAN GAS IN A NOVELLUS CONCEPT-2 CHEMICAL VAPOR DEPOSITION TOOL"; www.dupont.com/zyron/pdf/southwest_2002.pdf .	
		"REDUCING PFC EMISSIONS; A TECHNOLOGY UPDATE"; 1/7/2000 Future Fab Volume 9; Montgomery Research, Inc.; www.future-fab.com/documents.asp?grID=273&d_ID=1184 .	

Examiner Signature		Date Considered	
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